



Rika Taslim <rikataslim@gmail.com>

Invitation to review revision for Chinese Journal of Chemical Engineering

1 message

Chinese Journal of Chemical Engineering <em@editorialmanager.com>

Sat, Feb 19, 2022 at 8:01 AM

Reply-To: Chinese Journal of Chemical Engineering <cjche@elsevier.com>

To: Rika Taslim <rikataslim@gmail.com>

Manuscript Number: CJCHE-D-21-01574R1

Self-deposition for N-doping mesoporous carbon nanosheet with supercapacitor application

Juan Du; Aibing Chen; Senlin Hou; Xueqing Gao

Dear Dr Taslim,

I would like to invite you to review the above referenced revised manuscript submitted by Dr. Aibing Chen, as you kindly reviewed the previous version of this manuscript. Anonymised reviewer comments to author for the previous version are included below.

You should treat this invitation, the manuscript and your review as confidential. You must not share your review or information about the review process with anyone without the agreement of the editors and authors involved, even after publication. This also applies to other reviewers' "comments to author" which are shared with you on decision (and vice versa). For more information please visit: http://service.elsevier.com/app/answers/detail/a_id/14156/supporthub/publishing/

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Kind regards,

Guangsheng Luo
Associate editor
Chinese Journal of Chemical Engineering

Comments to author for previous version:

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Rika Taslim <rikataslim@gmail.com>

Thank you for reviewing for Chinese Journal of Chemical Engineering

1 message

Chinese Journal of Chemical Engineering <em@editorialmanager.com>

Fri, Mar 18, 2022 at 12:03 PM

Reply-To: Chinese Journal of Chemical Engineering <cjche@elsevier.com>

To: Rika Taslim <rikataslim@gmail.com>

Manuscript Number: CJCHE-D-21-01574R1

Self-deposition for N-doping mesoporous carbon nanosheet with supercapacitor application

Juan Du; Aibing Chen; Senlin Hou; Xueqing Gao

Dear Dr Taslim,

Thank you for reviewing the above referenced manuscript. I greatly appreciate your contribution and time, which not only assisted me in reaching my decision, but also enables the author(s) to disseminate their work at the highest possible quality. Without the dedication of reviewers like you, it would be impossible to manage an efficient peer review process and maintain the high standards necessary for a successful journal.

I hope that you will consider Chinese Journal of Chemical Engineering as a potential journal for your own submissions in the future.

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Kind regards,

Guangsheng Luo
Associate editor
Chinese Journal of Chemical Engineering

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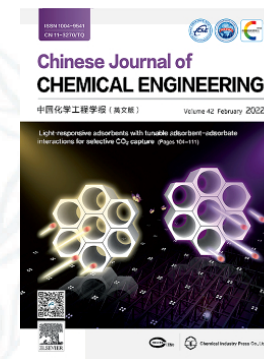
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Chinese Journal of Chemical Engineering

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